

IN THE CLAIMS

Please cancel claim 12 without prejudice or disclaimer as to its subject matter and amend claims 1, 2, 5-11 and 13-20 as follows and as follows:

1 1. (Currently Amended) A filter ~~for a plasma display panel~~, comprising:

2 a substrate;

3 a conductive material pattern ~~formed~~ arranged on the substrate, the conductive material
4 pattern comprising a conductive material, the conductive material having a pattern;

5 a negative photoresist pattern; patterned on the substrate on portions not covered by the
6 conductive material pattern to complement the conductive material pattern, the negative
7 photoresist pattern comprising a negative photoresist material that comprises a pigment and a dye
8 that cuts off light [[in]] of a specific wavelength range, as well as the negative photoresist
9 material further comprising a material that prevents external light from being reflected; and

10 a plated mesh ~~formed~~ arranged on a conductive material pattern.

1 2. (Currently Amended) The filter of claim 1, the negative photoresist pattern material
2 comprising a material selected from the group consisting of a transparent acryl group and a
3 phenol group.

1 3. (Original) The filter of claim 1, the dye comprising an organic compound selected from
2 the group consisting of an imonium group and a phthalocyanin group, the pigment comprising an

3 organic compound of the imonium group, the dye blocking near infrared rays.

1 4. (Original) The filter of claim 1, the dye comprising an organic compound selected from
2 the group consisting of an imonium group and a phthalocyanin group, the pigment comprising an
3 organic compound of the imonium group, the dye blocking light having a wavelength near 590
4 nm.

1 5. (Currently Amended) The filter of claim 1, [[the]] a combined thickness of the
2 conductive material pattern and the plated mesh ~~formed~~ arranged thereon being in a range of 1 to
3 50 μ m.

1 6. (Currently Amended) The filter of claim 1, wherein said material ~~preventing the that~~
2 prevents external light from being reflected being selected from the group consisting of a metal
3 powder and an inorganic metal oxide.

1 7. (Currently Amended) The filter of claim 1, the filter being formed by a process
2 comprising: ~~A method of manufacturing a filter for a plasma display panel, the method~~
3 ~~comprising the steps of:~~

4 coating an entire surface of [[a]] the substrate with a layer of [[a]] the conductive
5 material;

6 forming a predetermined positive photoresist pattern on the conductive material by

7 applying the photoresist, exposing the photoresist and developing the exposed photoresist;
8 etching exposed portions of the conductive material;
9 removing said patterned positive photoresist leaving a patterned the conductive material
10 pattern on the substrate;
11 coating said entire surface of the substrate having the patterned conductive material
12 pattern with a layer of the negative photoresist material that comprises a dye and a pigment that
13 cuts off light in a specific wavelength range, the negative photoresist further comprising a
14 material preventing external light from being reflected;
15 exposing the negative photoresist material by illuminating said substrate from a side
16 opposite from said surface containing said patterned conductive layer material pattern and the
17 negative photoresist material;
18 developing the exposed negative photoresist material to form [[a]] the negative
19 photoresist pattern exposing said patterned conductive material pattern; and
20 forming [[a]] the plated mesh on the exposed conductive material pattern by electrical
21 plating.

1 8. (Currently Amended) The method filter of claim 7, wherein the negative photoresist
2 material comprises a material selected from the group consisting of a transparent acryl group and
3 a phenol group.

1 9. (Currently Amended) The method filter of claim 7, the dye comprises an organic

2 compound of an imonium group, and the pigment comprises an organic compound of the
3 imonium group, the dye filtering out near infrared rays.

1 10. (Currently Amended) The method filter of claim 7, wherein the dye is an organic
2 compound of an imonium group or a phthalocyanin group, and the pigment is an organic
3 compound of the imonium group, the dye blocking light having a wavelength of about 590 nm.

1 11. (Currently Amended) The filter of claim 1, the filter being formed by a process
2 comprising: A method for making a filter for a plasma display panel, comprising the steps of:
3 forming the a patterned layer of a conductive material pattern on one a first side of a
4 transparent the substrate;

5 applying a layer of the negative photoresist material on said patterned first side of said
6 substrate;

7 exposing a pattern in said layer of negative photoresist material by illuminating a side of
8 said substrate opposite said patterned first side;

9 developing said layer of negative photoresist material resulting in said negative
10 photoresist pattern exposing only portions on said one side of said substrate patterned by the
11 conductive material; and

12 increasing [[the]] a thickness of said conductive material pattern on said first on said one
13 side of said substrate by electroplating.

1 Claim 12 (Canceled)

1 13. (Currently Amended) The method filter of claim 11, said patterned conductive
2 material pattern being formed by a process comprising:

3 forming a blanket layer of the conductive material; ;

4 applying, patterning, and developing a positive photoresist layer on the blanket
5 conductive layer of conductive material;

6 then etching the blanket layer of conductive material layer with patterned photoresist
7 thereon; and then before

8 removing the patterned positive photoresist.

1 14. (Currently Amended) The method filter of claim 13, said blanket layer of conductive
2 material being formed by sputtering.

1 15. (Currently Amended) The method filter of claim 11, the process further comprising
2 adding additives to said negative photoresist prior to said applying step, the additives serving
3 being adapted to filter out near infrared wavelengths.

1 16. (Currently Amended) The method filter of claim 11, said conductive material pattern
2 adapted to serve patterned layer of said conductive material serves as a mask in said exposing
3 step.

1 17. (Currently Amended) A filter for a plasma display, comprising:
2 a substrate that is transparent to light;
3 a conductive mesh pattern arranged formed on one side of the substrate; and
4 a non conductive material disposed arranged on said one side of said substrate at
5 locations absent said conductive mesh.

1 18. (Currently Amended) The filter of claim 17, said conductive mesh pattern and said
2 non-conductive material having equal depths between 1 and 50 microns.

1 19. (Currently Amended) The filter of claim 17, said non conductive material being
2 comprising negative photoresist containing comprising additives.

1 20. (Currently Amended) The filter of claim 17, said conductive mesh pattern being
2 electrically grounded.

1 21. (Currently Amended) The filter of claim 17, said conductive mesh pattern having a
2 grid pattern.

1 22. (Currently Amended) The filter of claim [[17]] 19, said additives comprising a dye.